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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Shigeharu Monoe Art Unit: Unknown Serial No.: New Application Examiner: Unknown

Filed : June 26, 2003

Title : METHOD FOR MANUFACTURING SEMICONDUCTOR DEVICE

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Copies of the references listed on the attached form PTO-1449 are enclosed.

This statement is being filed with the application. Please apply any charges or credits to Deposit Account No. 06-1050.

Respectfully submitted,

Date: June 26, 2003

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Substitute Form PTO-1449 (Modified)	U.S. Department of Commerce Patent and Trademark Office		Application No. New Application	
	losure Statement plicant	Applicant Shigeharu Monoe		
(Use several sheets if necessary) (37 CFR §1.98(b))		Filing Date June 26, 2003	Group Art Unit	

U.S. Patent Documents							
Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
	AA	6,235,558	05/22/2001	Oda et al.			03/31/2000
	AB	US 2001/0030322 A1	10/18/2001	Yamazaki et al.			02/02/2001
	AC	US 2001/0035526 A1	11/01/2001	Yamazaki et al.			04/24/2001
	AD	US 2001/0055841 A1	12/27/2001	Yamazaki et al.			04/12/2001
	AE	US 2002/0158288 A1	10/31/2002	Yamazaki et al.			02/21/2002
	AF						
	AG						

Foreign Patent Documents or Published Foreign Patent Applications								
Examiner	Desig.	Document	Publication	Country or	Class	Cubalasa		lation
Initial	ID_	Number	Date	Patent Office	Class	Subclass	Yes	No
	AH	07-106346	04/21/1995	Japan			ABS	
/	AI	08-45906	02/16/1996	Japan			ABS	
✓	AJ	10-10752	01/16/1998	Japan			ABS	
	AK	2000-294787	10/20/2000	Japan			ABS	
	AL	EP 1 128 430 A2	08/29/2001	Europe				
	AM	2001-313397	11/09/2001	Japan			ABS	
/	AN	2002-14337	01/18/2002	Japan			ABS	

	Other Documents (include Author, Title, Date, and Place of Publication)				
Examiner	Desig.				
Initial	ID	Document			
	AO	M. Nagase et al.; "Study of sub-30nm gate Etching Technology"; 2001 Dry Process International Symposium; pp. 17-22; 2001			
	AP				
	AQ				
	AR				

Examiner Signature	Date Considered				
EXAMINER: Initials citation considered, Draw line through citation if not in conformance and not considered. Include copy of this form with					
next communication to applicant.					